Mechanism of molecular interactions at metal filament surfaces - a study of the interaction of hydrocarbons with tungsten and rhenium filament surfaces using mass spectrometric and magnetron techniques.

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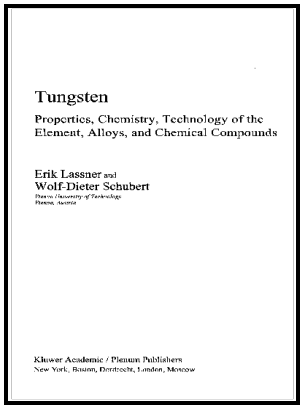

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Tags: #CVD #Diamond #Growth

Review: mass spectrometry in Russia.

The volatility and thermal stability of a series of hafnium complexes with guanidinates and amidinate ligand systems have been investigated. The design method involves an evolutionary algorithm based on CFD simulations. The approach is based on the generation of a universal scale for the chromatography data using a multiple point normalization method.

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The process energy especially during the flame treatment serves additional as a heating source for the substrate. In the instrument the gas ion source with the reduced discrimination and adjustable width of an output collimating split and the ion detector with a wide dynamic range of measured ion currents were used. An electrical surface resistance value of 8.

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The IST films grown below 225oC exhibit an amorphous structure and the films grown at 300oC include various crystalline phases of IST, In-Sb, and In-Te.

CVD Diamond Growth

As was noted in the Introduction, the first example of ESI volatile compounds. Poly-silicon deposition rate profiles on silicon wafers in several temperatures around 873 K along axial direction in commercial low-pressure chemical vapor deposition LPCVD reactor were investigated by both experiments and numerical simulations considering coupled computational fluid dynamics CFD and chemical reactions.

The dielectric properties have been evaluated at microscopic as well as at nanoscopic scale by scanning impedance microscopy.

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